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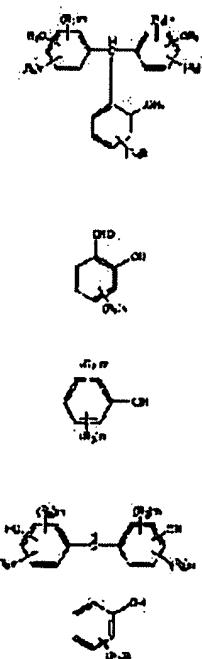
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(54) NEW TRISPHENOL ETHERS



(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a new trisphenol ether having high solubility in various polymer substances including a photoresist and an organic solvent, useful as an acid decomposable dissolution inhibitor for a chemical amplification type resist composition.

SOLUTION: This trisphenol ether is shown by formula I (R1 is t-butoxycarbonylmethyl or tetrahydropyranyl; R2 is a 1-4C alkyl; R3 is a 5-6C cycloalkyl; (m) is 0-3, (n) is 0-2 and $0 \leq m+n \leq 3$; (k) is 0 or 1) such as bis(2-methyl-4-t-butoxycarbonylmethoxy-5-cyclohexylphenyl)-methyl-2-t-butoxycarbonylmethoxybenzene. The compound of formula I is obtained, for example, by condensing a hydroxyl group-substituted benzaldehyde derivative of formula II (R4 is a 1-4C alkyl or alkoxy) with a phenol compound of formula III in the presence of an acid catalyst to give a trisphenol compound of formula IV and etherifying the compound.

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